#### NARROW GAP ELECTRONEGATIVE CAPACITIVE DISCHARGES AND STOCHASTIC HEATING

M.A. Lieberman

Department of Electrical Engineering and Computer Sciences University of California Berkeley, CA 94720

Collaborators: E. Kawamura, D.B. Graves, and A.J. Lichtenberg, UC Berkeley C. Lazzaroni and P. Chabert, Ecole Polytechnique, France J. Gudmundsson, Shanghai Jiao Tong U; Science Institute, U. Iceland

Motivation: widely used for thin film etch and deposition

Download this talk:

http://www.eecs.berkeley.edu/~lieber

LiebermanPSC13

PLASMA

#### OUTLINE

- PIC simulations of narrow gap oxygen discharges
- Equilibrium discharge model
- Stochastic (collisionless) heating

LiebermanPSC13

#### **DISCHARGE CONFIGURATION**

- Oxygen at 10–100 mTorr,  $V_{\rm rf} = 500-2000 {\rm V}$
- 1D plane-parallel geometry  $(\sim 1-10 \text{ cm gap length } L)$
- Usual model is stratified discharge with electronegative (EN) core and electropositive (EP) edge



• As L is decreased, the EP edge can disappear and new interesting phenomena are found

LiebermanPSC13

University of California, Berkeley

PLASMA -

# PIC SIMULATIONS AND EQUILIBRIUM MODELING (Vary gap length L at p=50 mTorr, $V_{rf} = 500 \text{ V}$ )

LiebermanPSC13

University of California, Berkeley

#### L=4.5 cm (EP EDGE EXISTS)



#### L=2.5 cm (NO EP EDGE)



6

#### EEDF'S AND DENSITY DETAILS



7

## TIME-VARYING DENSITY (L=2.5 cm, NO EP EDGE)



University of California, Berkeley

2

## MODELING CONSIDERATIONS

- EP edge exists (larger gap lengths L)
  - Bi-Maxwellian EEDF
  - About half the ion flux generated in sheath/EP edge
  - Usual Child law rf sheath
  - Usual positive collisionless heating in sheath
- No EP edge (smaller gap lengths L)
  - Maxwellian EEDF
  - Over half the ion flux generated in sheath % f(x)=f(x)
  - Attachment in sheath is important
  - Unusual rf sheath containing negative ions
  - Negative collisionless heating in sheath, positive in core
- Models developed:
  - model with some inputs from PIC results
  - self-consistent model

 ${\it LiebermanPSC13}$ 

PLASMA

## MODEL WITH SOME INPUTS FROM PIC

- Rate coefficients and collisional energy losses using PIC EEDF
- Power deposition in core from PIC results
- Solid lines (2-region model (4) with EP edge); Dashed lines 10<sup>16</sup> (1-region model without EP edge); circles (PIC results) 10<sup>15</sup>



• Reasonable agreement between model and PIC results (submitted to Physics of Plasmas, 2013)

## STOCHASTIC (COLLISIONLESS) HEATING

LiebermanPSC13

University of California, Berkeley -

1.

- PLASMA

## PIC RESULTS FOR VARIOUS GAPS L (50 mT, 500 V)

- Stochastic heating small at transition where EP edge disappears
- EP edge exists  $\Rightarrow$  positive heating in sheath, negative in core
- ing in sheath, positive in core

L=4.5 cm

p<sub>ohr</sub>

0.02

x (m)

0.03

5000

3000

2000

1000

-1000

0

4000 Large

pos

0.01





## INTEGRATED $S_{stoc}(x)$ FOR VARIOUS GAPS L

• Integrate power density  $p_{\text{stoc}}(x)$  from electrode toward discharge midplane



- Large  $L \Rightarrow n_e(\text{core}) > n_e(\text{sheath})$  $\Rightarrow$  positive heating in sheath, negative heating in core
- Small  $L \Rightarrow n_e(\text{sheath}) > n_e(\text{core})$  $\Rightarrow$  negative heating in sheath, positive heating in core

LiebermanPSC13

University of California, Berkeley

#### **TWO-STEP DENSITY MODEL**

- 1. I.D. Kaganovich, Phys. Rev. Lett. 89, 265006 (2002).
- E. Kawamura, M.A. Lieberman and A.J. Lichtenberg, Phys. Plasmas 13, 053506 (2006).

#### Use to investigate stochastic heating

University of California, Berkeley —

LiebermanPSC13



## SUMMARY

- A transition from an EN discharge with an EP edge, to a narrower gap discharge with no EP edge, was investigated with PIC simulations and modeling
- The effects of a bi-Maxwellian EEDF, with an EP edge, and sheath attachment and core uncovering, with no EP edge, need to be taken into account in modeling
- A transition from sheath to internal stochastic heating after the EP edge disappears is observed, and is being studied with a fixed ion, two-step density, PIC simulation

LiebermanPSC13